



CDMMS MEETING

Co-hosted with RPI's
CENTER FOR INTEGRATED ELECTRONICS



RPI – Center for Industrial Innovation
Wednesday, September 21st, 2011, 6-8PM

Dinner Menu

Taco Bar: Beef, Chicken, or Veggie
side dishes, beverages, and dessert also included

Cost: \$5/students • \$10/members • \$15/non-members • \$5/talk only

New membership: \$25/professionals • \$10/students

PLEASE EMAIL IAN TO RSVP WITH DINNER OF CHOICE BY SEPT. 19TH
spinelli@ge.com

James J. Demarest

Microscopy of Semiconductors – An overview of Microscopy Techniques for the
Observation and Analysis of Semiconductors

Bio. James Demarest received his BS in Materials Science and Engineering in 1996 from Lehigh University. He then continued his studies at the University of Virginia and graduated with a Ph.D. in Materials Science and Engineering in 2001. While at UVA, his principle interests lay with transmission electron microscopy of semiconductor devices and materials along with focused ion beam microscopy and scanning electron microscopy. Jay then joined IBM in 2001 and began performing reliability failure analysis on developing technologies. In 2007 Dr. Demarest transitioned to IBM's Albany nanotechnology facility in Albany, NY heading up the physical characterization lab. His interests currently include all aspects of electron microscopy, ion microscopy, and reliability failure analysis including defect isolation, low-k and ultra low-k dielectric materials, and emerging technologies. In addition, Dr. Demarest has written or coauthored more than 21 papers and 9 US patents.



For more info, visit www.CDMMS.org

